

METHOD AND APPARATUS FOR ADJUSTING THE THICKNESS OF A  
THIN LAYER OF SEMICONDUCTOR MATERIAL

ABSTRACT

5           A method for adjusting the thickness of a thin  
semiconductor material layer. The method includes  
measuring the layer to establish a thickness profile,  
determining thickness adjustment specifications from the  
measured thickness profile, and adjusting the thickness  
10 of the layer in accordance with the specifications by  
sacrificial oxidation. An apparatus for adjusting the  
thickness of a thin layer of semiconductor material  
according to this method is also disclosed.

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